



Form PTO 1449 (Modified)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY DOCKET NO. 211147US99		SERIAL NO. 09/903,784		
LIST OF REFERENCES CITED BY APPLICANT				APPLICANT Aroon V. TUNGARE, et al.				
				FILING DATE July 13, 2001		GROUP 2826		
U.S. PATENT DOCUMENTS								
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE	
PE ↓	ZV	5,122,679	06/16/92	ISHII ET AL				
	ZW	6,232,806	05/15/01	WOESTE ET AL				
	ZX	5,430,397	07/04/95	ITOH ET AL				
	ZY	6,151,240	11/21/00	SUZUKI				
	ZZ	6,528,374	03/04/03	BOJARCZUK, JR ET AL				
	A1	6,589,887	07/08/03	DALTON ET AL				
	A2	5,064,781	11/12/91	CAMBOU ET AL				
	A3	2002/0052061	05/02/02	FITZGERALD				
	A4	5,696,392	12/09/97	CHAR ET AL				
	A5	5,986,301	11/16/99	FUKUSHIMA ET AL				
	A6	6,329,277	12/11/01	LIU ET AL				
	A7							
	A8							
	A9							
FOREIGN PATENT DOCUMENTS								
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES NO			
P3 ↓	CCS	WO 99/67882	12/29/99	WIPO				
	CCT	WO 95/02904	01/26/95	WIPO				
	CCU	WO 02/009150	01/31/02	WIPO				
	CCV	0 766 292	04/02/97	EUROPE				
	CCW	198 29 609	01/05/00	GERMANY				
	CCX	1 069 605	01/17/01	EUROPE				
	CCY	0 828 287	03/11/98	EUROPE				
	CCZ	1 176 230	01/30/02	EUROPE				
OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)								
P6	LLAP	YI W. et al; "Mechanism of cleaning Si (100) surface using Sr and SrO for the growth of crystalline SrTiO/sub 2/films" Journal of Vacuum Science & Technology, Vol. 20, No. 4, July 2002 (2002-07) pp. 1402-1405						
P6	LLAQ	XIAMING HU et al; "Sr/Si template formation for the epitaxial growth of SrTiO/sub 3/on silicon" Materials Research Society Proceedings, Vol. 716, 2002, pp. 261-266						
	LLAR							
	LLAS					<input type="checkbox"/> Additional References sheet(s) attached		
Examiner <i>[Signature]</i> <i>PAU 6206</i>					Date Considered <i>10/30/02</i>			
*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								